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45. (Amended) The method according to Claim 42, wherein a plasma power of 300 watts to 5000 watts on a time average is injected into the inductively coupled plasma and that the generated individual pulse powers of the radio-frequency power pulses are between 300 watts and 20 kilowatts.

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47. (Amended) The method according to Claim 42, wherein during the etching, one of a static and time-variable magnetic field is generated, the direction of which is at least one of approximately and predominantly parallel to a direction defined by the connecting line of the substrate and the inductively coupled plasma.

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50. (Amended) The method according to Claim 42, wherein one of a constant and time-variable radio-frequency power is applied to the substrate via a substrate voltage generator.

51. (Amended) The method according to Claim 50, wherein the pulse duration of the radio-frequency power injected into the substrate is between one to one hundred times the period of oscillation of the high-frequency fundamental component of the radio-frequency power.

52. (Amended) The method according to Claim 50, wherein the radio-frequency power applies a time-average power of 5 watts to 100 watts to the substrate, a maximum power of an individual radio-frequency power pulse being one to 20 times the time average power.

53. (Amended) The method according to Claim 51, wherein the frequency of the injected radio-frequency power is between 100 kHz to 100 MHz and a pulse-to-pause ratio of the injected radio-frequency pulses is between 1:1 and 1:100.

54. (Amended) The method according to Claim 42, wherein the pulsing of the injected plasma power and one of the pulsing of the radio-frequency power injected into the substrate via the substrate voltage generator and a pulsing of the magnetic field, the pulsing of the injected plasma power and the pulsing of the radio-frequency power injected into the substrate via the substrate voltage generator are one of time-correlated and synchronized with

by end
each other.

[Please add new claims 61 to 73 as follows:]

61. (New) The method according to Claim 45, wherein the radio-frequency power pulses are between 2 kilowatts to 10 kilowatts.

62. (New) The method according to Claim 47, wherein one of the static and time-variable magnetic field is one of periodically varying and pulsed magnetic field.

63. (New) The method according to Claim 50, wherein one of the constant and time-variable radio frequency power is a pulsed, radio-frequency power.

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64. (New) The method according to Claim 50, wherein a pulse duration of the radio-frequency power injected into the substrate is between one to ten times a period of oscillation of the high-frequency fundamental component of the radio-frequency power.

65. (New) The method according to Claim 51, wherein the pulse duration is between one to ten times.

66. (New) The method according to Claim 52, wherein the maximum power of an individual radio-frequency power pulse is between twice to 10 times the time average power.

67. (New) The method according to Claim 53, wherein the frequency of the injected radio-frequency power is 13.56 MHz.

68. (New) The method according to Claim 53, wherein the pulse-to-pause ratio of the injected radio-frequency pulses is between 1:1 and 1:10.

69. (New) The method according to Claim 42, wherein the pulsed plasma power is in a kilowatt range.

70. (New) The method according to Claim 42, wherein the pulsed plasma power is